



華瑞功率電子股份有限公司



CET-MOS Company Profile



2017

10F, No.176, Jiankang Rd., Chung-Ho Dist.,
New Taipei City, Taiwan. R.O.C. 23585
TEL:886-2-22229138 FAX:886-2-22223833

Outline



About CET-MOS

Overview / Background / Organization



Packages & End products

Scope / Advantages / Reliability Qualification



CET-MOS Technologies

Design Flow / Technology Roadmap



Partners and Support



Conclusion

Overview

CET-MOS at a glance

EST. DATE :

April, 2012.

EMPLOYEES :

60 People.

CAPITAL :

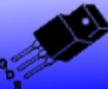
USD 45 Million.

LOCATION :

**10F., No. 176,
Jiankang Rd.,
Chung-Ho Dist.,
New Taipei City,
Taiwan.**



Product customized
SPECIALTIES: Fab Process setup abilities
Reliability testing team



Background

Certification:
ISO9002
ISO9001
QS9000

**1st MOSFETs
Design House
in Taiwan**

**Broad variety
of MOSFETs
product
(-200V~1000V)**

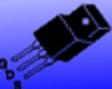
**1st MOSFETs
Package / new
structure
patent**

**0.2um Power
MOSFETs
product**

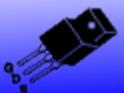
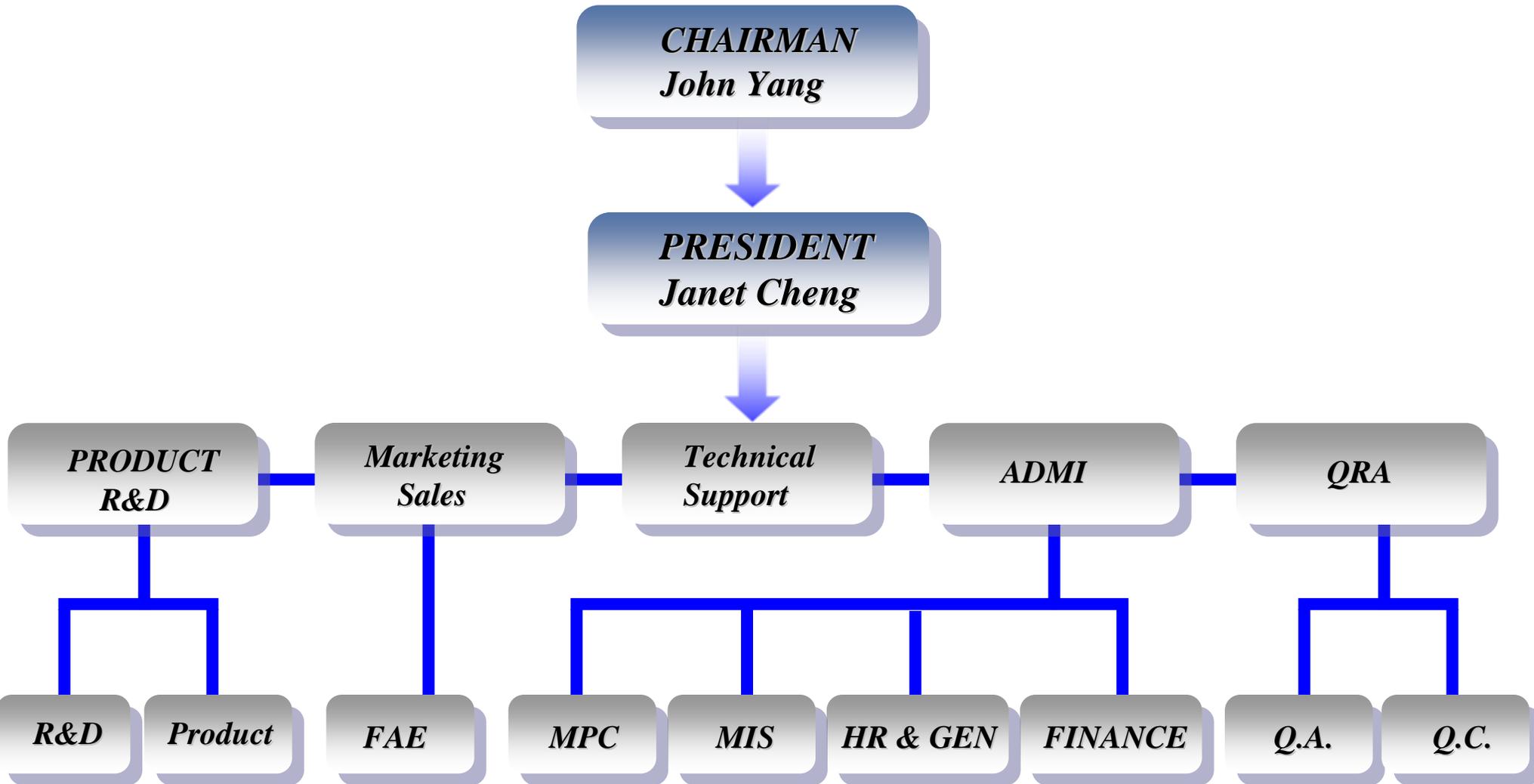
Chino-Excel Technology Corporation

Experience inherited

CET-MOS Corporation



Organization



Series of Package Type

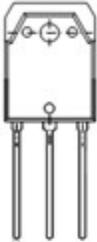
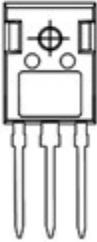
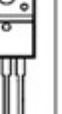
Available Package

2010

2013

2016

CET POWER MOSFET PACKAGE

TO-3P	DFN2X2	DFN3X3	PR-PACK5X6	SO-8	TSSOP8
	 2.0X2.0 (2.0X2.0)	 3.0X3.0 (3.0X3.0)	 5.1X6.15 (5.1X5.9)	 5.0X6.20 (5.0X4.06)	 3.1X6.6 (3.1X4.5)
	TSOP6	SOT323	SOT-223	SOT-23(E)	SOT-23
	 3.10X3.0 (3.1X1.8)	 2.2X2.45 (2.2X1.35)	 6.8X7.3 (6.8X3.7)	 3.04X2.95 (3.04X1.70)	 3.04X2.95 (3.04X1.9)
	SOT-89	TO-252	TO-251	TO-92	TO-263
 16.1X41.0 (16.1X20.55)					
TO-247					
	4.7X4.5 (4.7X2.69)	7.01X10.6 (7.01X8.41)	7.01X18.08 (7.01X8.43)	4.85X17.55 (4.85X4.85)	10.54X15.88 (10.54X11.05)
	TO-126F	TO-126	TO-262	TO-220F	TO-220
	 8.2X26.95 (8.2X11.2)	 8.05X26.85 (8.05X11.1)	 10.75X24.6 (10.75X10.95)	 10.36X30.75 (10.63X16.3)	 10.66X31.24 (10.63X16.51)
15.90X41.91 (15.90X21.34)					

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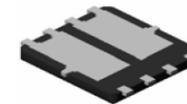
▪TO252-4



▪DFN2*2



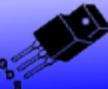
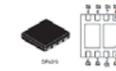
▪Power Pack 5*6 (dual)



▪Power Pack 5*6



▪DFN 3*3 (dual)



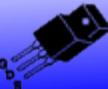
Capacity

Wafer capacity

Foundry Wafer Size	6"	6"	8"
Wafer Process	Planar	Trench	Trench
Capacity (pcs/Month)	15K (~23KK dies)	5K (~20KK dies)	10K (~180KK dies)

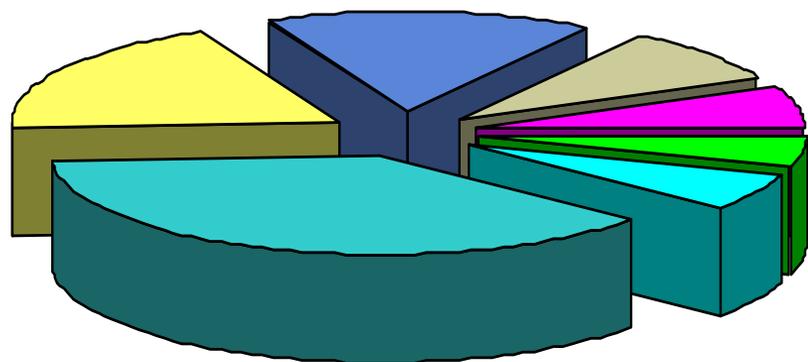
Package capacity

Package	Taiwan	China	Korea	Malaysia	Total Capacity (K)
SOP8	15,000	40,000		10,000	65,000
TSSOP08		25,000		10,000	35,000
TO-220	8,000	20,000	12,000		40,000
TO-220F		20,000	10,000		30,000
TO-263		10,000	8,000		18,000
TO-251	20,000	20,000	8,000		48,000
TO-252	20,000	20,000	8,000		48,000
TO-247		8,000	5,000		13,000
TO-3P		10,000	6,000		16,000
SOT-23	15,000	50,000			65,000
SOT-223		10,000			10,000
SOT-89		25,000			25,000
TSOP6		20,000			20,000
TO-92		25,000			25,000
PR PAK 3*3	10,000	15,000		6,000	31,000
SC70(SOT-323)		5,000			5,000
TO-126		5,000			5,000
PR PAK 5*6	5,000	5,000			10,000
TOTAL	88,000	333,000	57,000	26,000	509,000



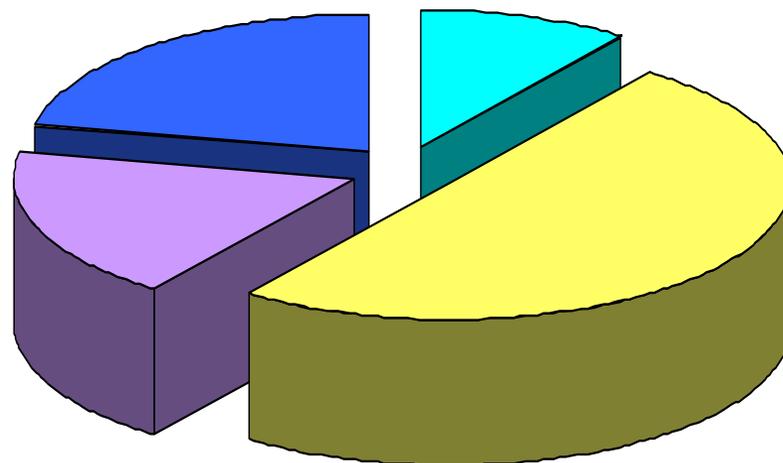
Scope

By Application



- Consumer 38%
- UPS 19%
- SPS 16%
- Power tool 9%
- DC Fan 7%
- Other 6%
- BMS 5%

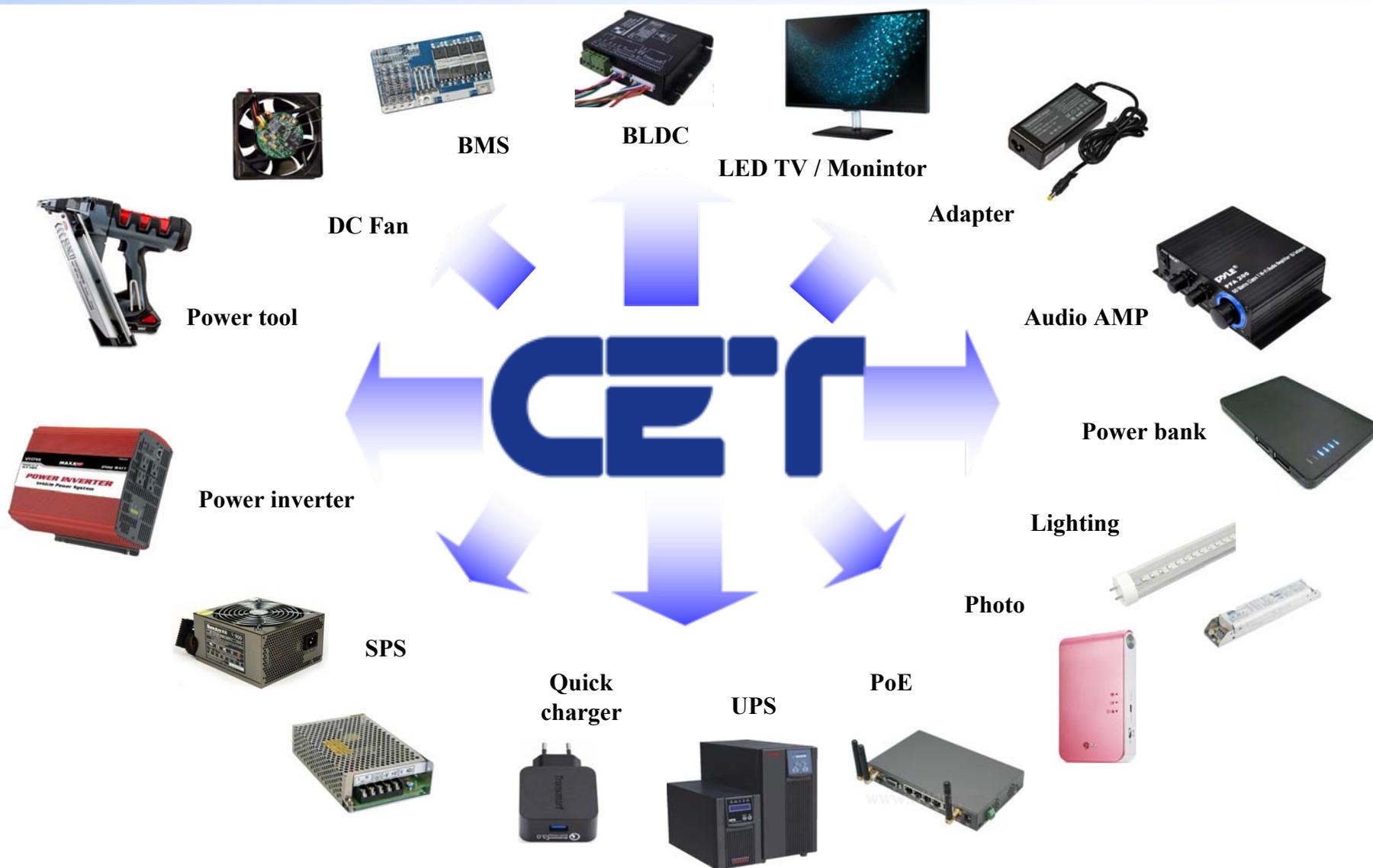
By Voltage (Include N/P MOS)



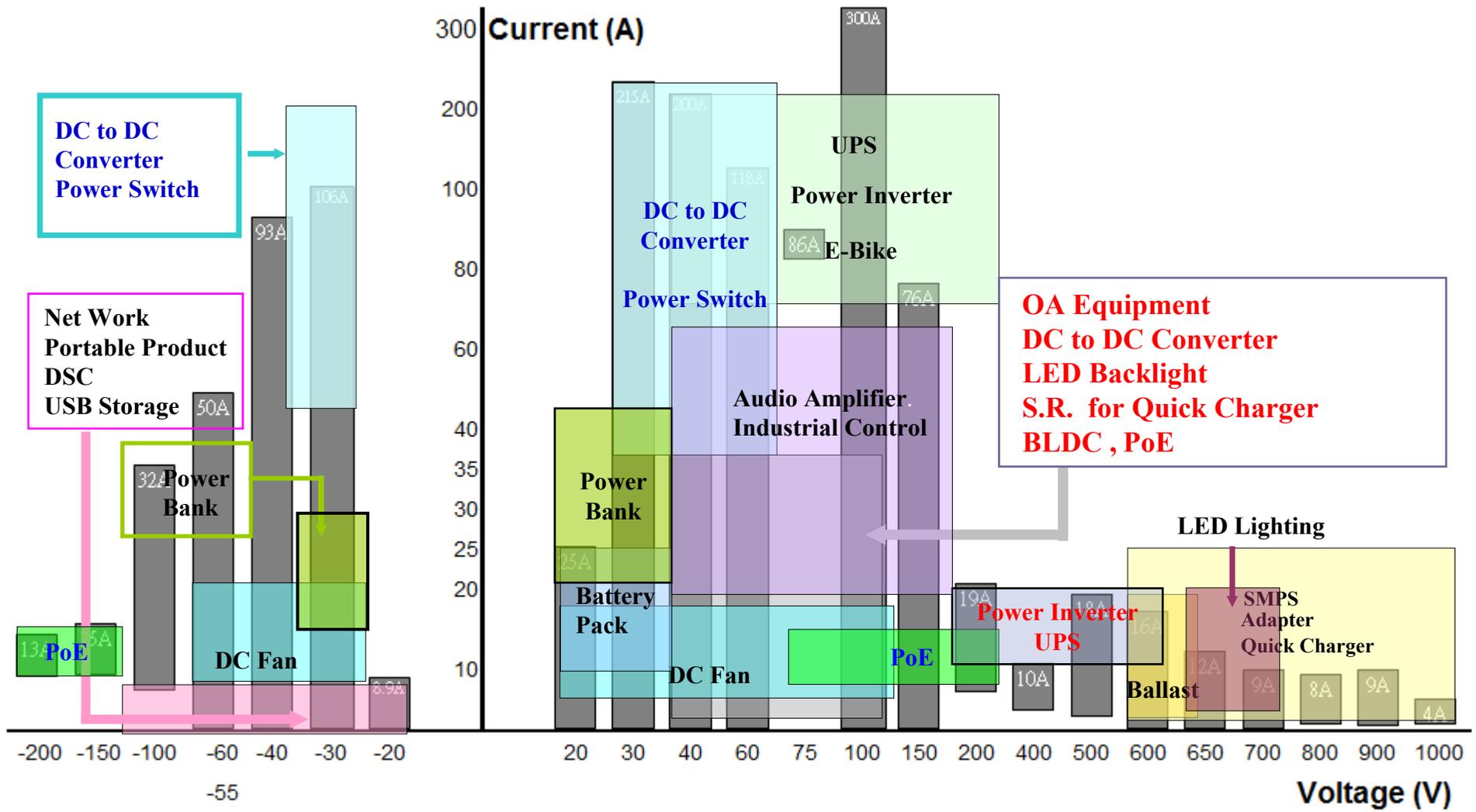
- 200V ~ -20V 10%
- 20V ~ 100V 50%
- 100V ~ 400V 18%
- 400V ~ 900V 22%



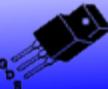
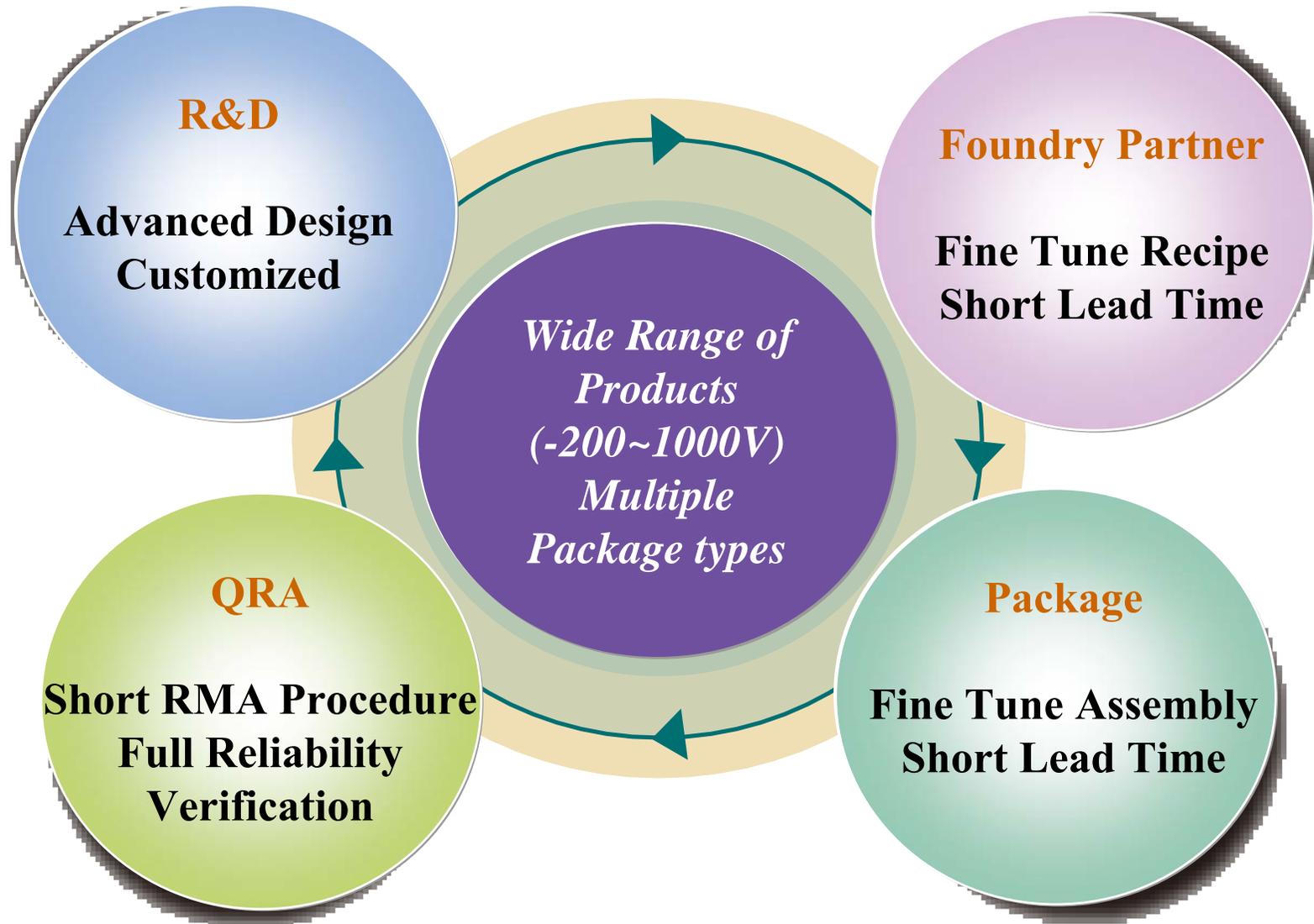
Field Application



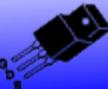
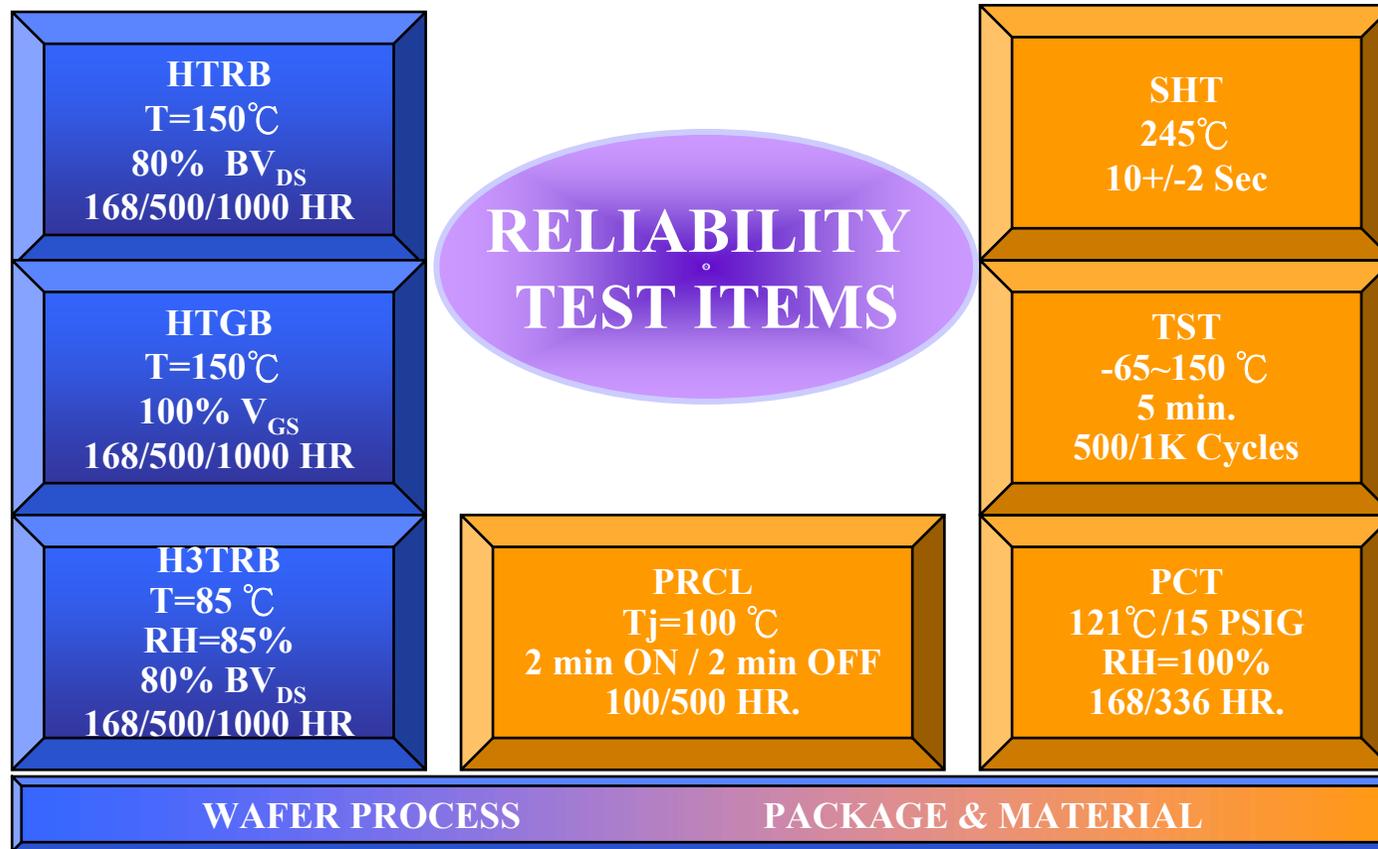
Power Device Application



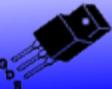
Advantages



Reliability Qualification



Design Flow

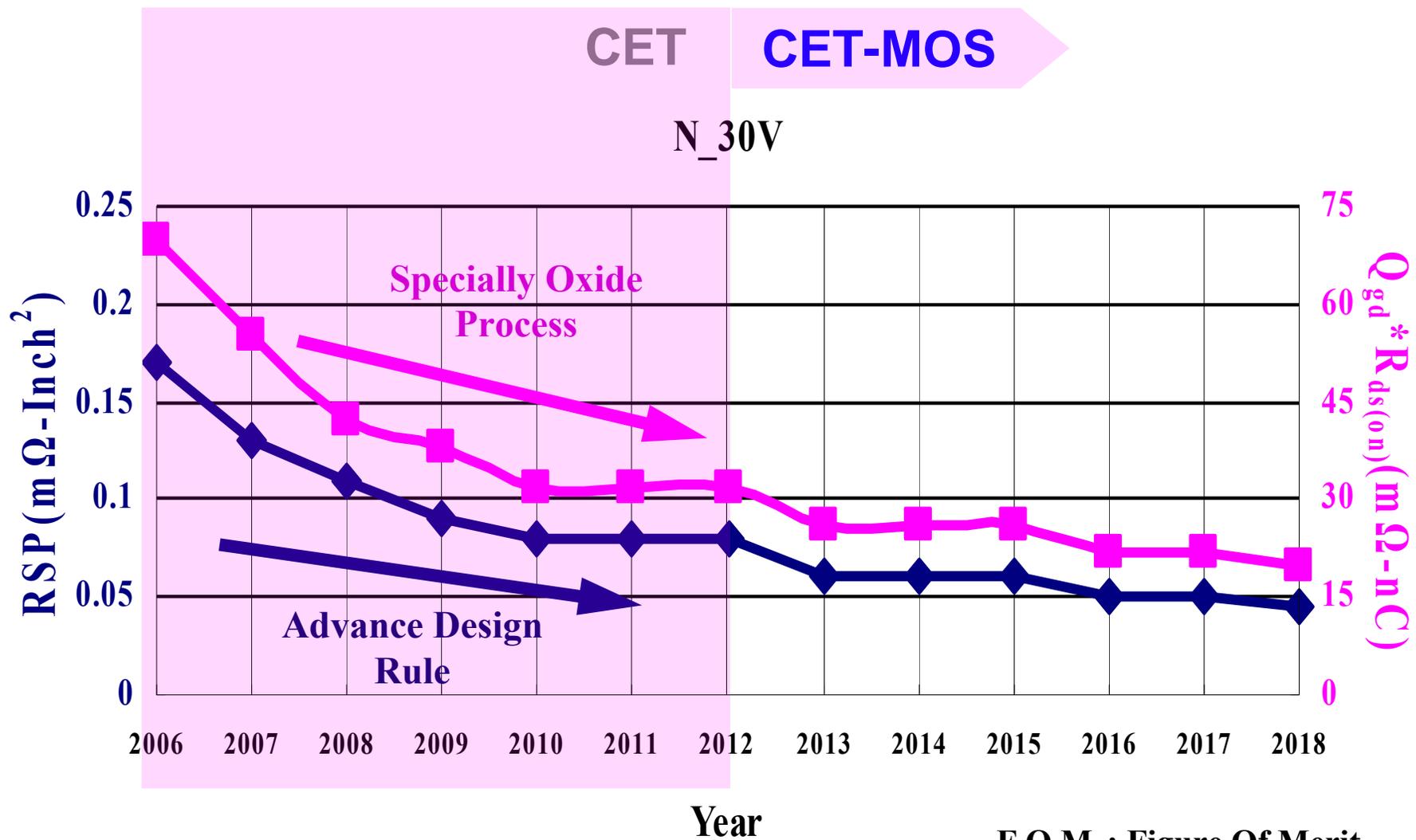


Technology Roadmap

	CET	CET-MOS		
	Available Technology	2013~2016	2017	2018
LOW VOLTAGE	<ul style="list-style-type: none"> .Low Q_{gd} (Special Oxide) .Low R_g Device .Ultra-low $R_{ds(on)}$ (High Density) .High Speed (Special Gate) .8" 650M cell 	<ul style="list-style-type: none"> .Ultra fast device .DFN 2X2 (small size) .Ultra-low $R_{ds(on)}$.Custom Specific .Design Service 	<ul style="list-style-type: none"> .Ultra fast device .DFN 2X2 (small size) .Ultra high UIS .Bottom Oxide .Customer made 	<ul style="list-style-type: none"> . 4 in 1 module .Ultra high UIS .Bottom Oxide .Clip Bonding PDS .Customer made
MIDDLE VOLTAGE	<ul style="list-style-type: none"> .Super Low $R_{ds(on)}$.High Switch Speed .ESD Device .Low Gate Charge .150V Trench Power MOS 	<ul style="list-style-type: none"> .Super low Rdson .Trench (-150V~200V) .High Ruggedness MOS .Custom Specific .Design Service 	<ul style="list-style-type: none"> .Trench (-150V~250V) .High Ruggedness Device .Split Gate Device .Custom Specific Design 	<ul style="list-style-type: none"> .Trench (300V ↗) .High Ruggedness Device .Split Gate Device .Custom Specific Design
HIGH VOLTAGE	<ul style="list-style-type: none"> .High Voltage to 800V .Low Gate Charge .Low Q_{gd} .LTO process (High UIS) .Custom Specific Design 	<ul style="list-style-type: none"> .High UIS High Voltage Power MOS (1000V) .Short terminal .Custom Specific .Design Service 	<ul style="list-style-type: none"> .Low Q_{gd} .High UIS High Voltage Power MOS (1000V) .Short terminal .Custom Specific Design 	<ul style="list-style-type: none"> .Low Q_{gd} .Compound Material .High dv/dt device .GaN on silicon .Custom Specific Design



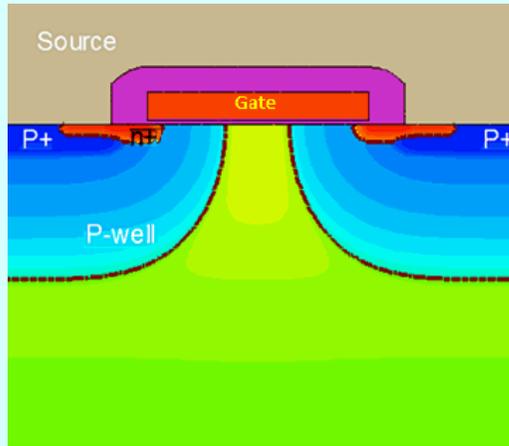
Technology Roadmap (F.O.M.)



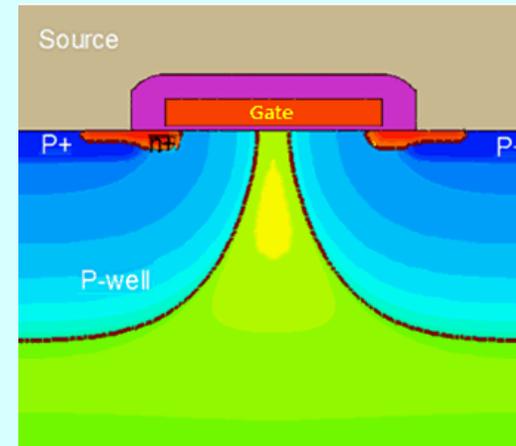
F.O.M. : Figure Of Merit



MOSFETs Technology



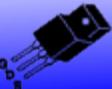
Traditional Planar NMOS



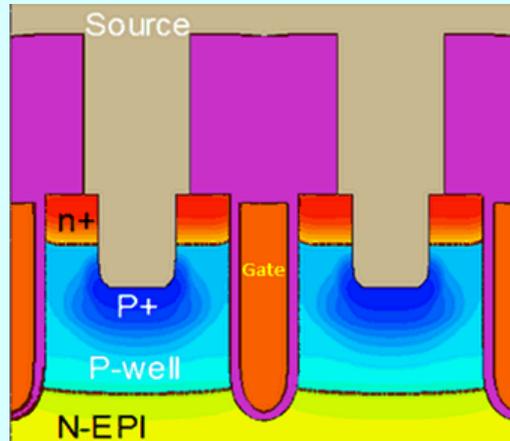
Low- Q_{gd} Planar NMOS

MOSFETs Technology Features

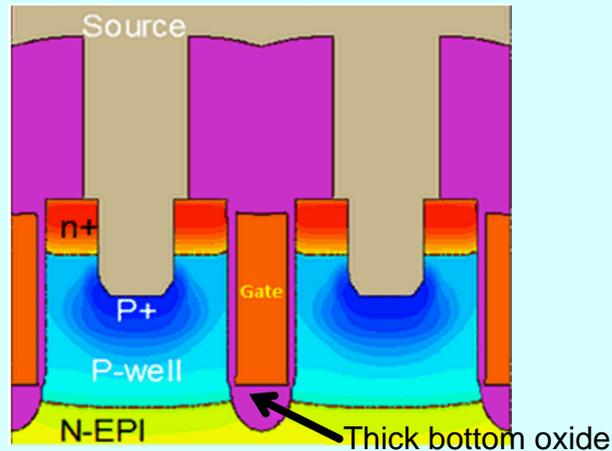
- Traditional Planar MOSFETs - High voltage.
- Low- Q_{gd} Planar MOSFETs - High density, Low- Q_{gd} , High UIS.



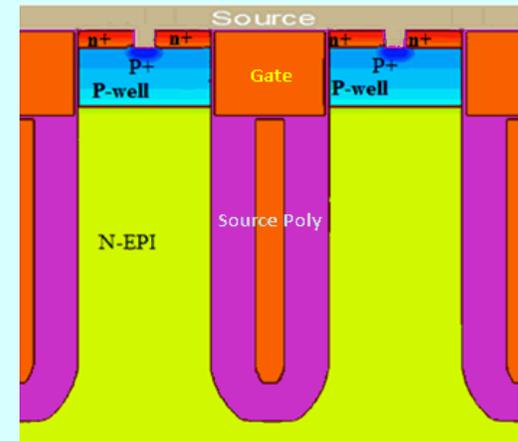
MOSFETs Technology



Traditional Trench
NMOS



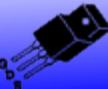
NMOS with thick
bottom oxide.



NMOS with split gate

MOSFETs Technology Features

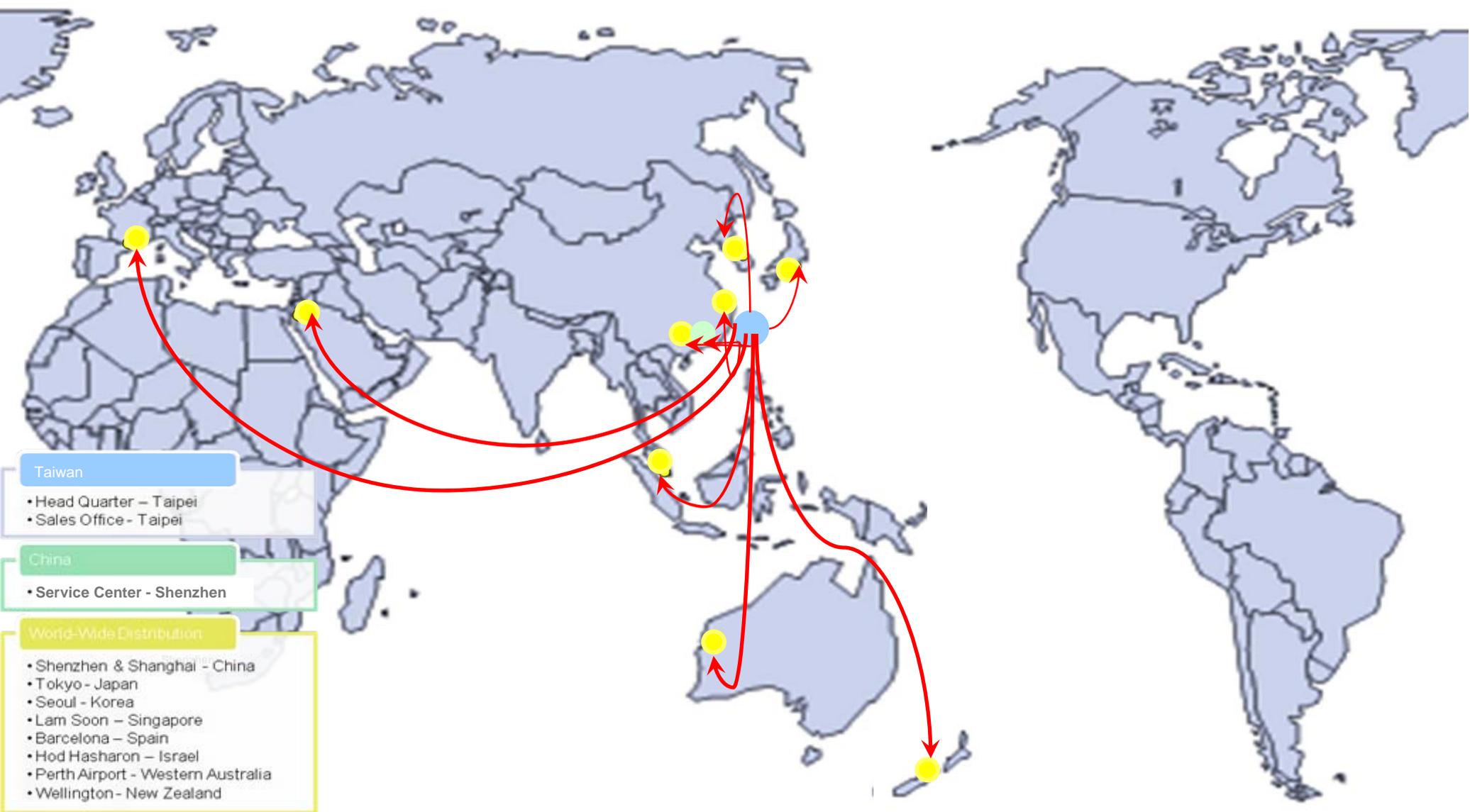
- Traditional Trench MOSFETs – High density, Low $R_{ds(on)}$.
- Thick Bottom Oxide Design– High density, Low $R_{ds(on)}$, Low Q_{gd} .
- Split Gate Structure– High density, Ultra-low $R_{ds(on)}$, Ultra-low Q_{gd} .



Partners

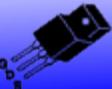


Global Support



Why CET-MOS?

Over 25 years experience from CET



CET-MOS will be your best partner

